Andre Anders

List of Publications by Year
in descending order

415 papers	16,305 citations	16437 64 h-index	24232 110 g-index
427 all docs	427 docs citations	427 times ranked	7777 citing authors

#	Article	IF	Citations
1	A structure zone diagram including plasma-based deposition and ion etching. Thin Solid Films, 2010, 518, 4087-4090.	0.8	641
2	Dynamically Modulating the Surface Plasmon Resonance of Doped Semiconductor Nanocrystals. Nano Letters, 2011, 11, 4415-4420.	4.5	491
3	Cathodic Arcs. Springer Series on Atomic, Optical, and Plasma Physics, 2008, , .	0.1	443
4	Nanoindentation and Nanoscratching of Hard Carbon Coatings for Magnetic Disks. Materials Research Society Symposia Proceedings, 1995, 383, 447.	0.1	356
5	Ion flux from vacuum arc cathode spots in the absence and presence of a magnetic field. Journal of Applied Physics, 2002, 91, 4824-4832.	1.1	342
6	Ion charge state distributions of vacuum arc plasmas: The origin of species. Physical Review E, 1997, 55, 969-981.	0.8	300
7	High power impulse magnetron sputtering: Current-voltage-time characteristics indicate the onset of sustained self-sputtering. Journal of Applied Physics, 2007, 102, .	1.1	287
8	Tutorial: Reactive high power impulse magnetron sputtering (R-HiPIMS). Journal of Applied Physics, 2017, 121, .	1.1	275
9	Hardness, elastic modulus, and structure of very hard carbon films produced by cathodicâ€arc deposition with substrate pulse biasing. Applied Physics Letters, 1996, 68, 779-781.	1.5	255
10	Metal plasma immersion ion implantation and deposition: a review. Surface and Coatings Technology, 1997, 93, 158-167.	2.2	239
11	Ion velocities in vacuum arc plasmas. Journal of Applied Physics, 2000, 88, 5618-5622.	1.1	229
12	Discharge physics of high power impulse magnetron sputtering. Surface and Coatings Technology, 2011, 205, S1-S9.	2.2	225
13	Regulation of the Î±â€secretase ADAM10 by its prodomain and proprotein convertases. FASEB Journal, 2001, 15, 1837-1839.	0.2	220
14	Approaches to rid cathodic arc plasmas of macro- and nanoparticles: a review. Surface and Coatings Technology, 1999, 120-121, 319-330.	2.2	206
15	A discussion on the absence of plasma in spark plasma sintering. Scripta Materialia, 2009, 60, 835-838.	2.6	204
16	Review of cathodic arc deposition technology at the start of the new millennium. Surface and Coatings Technology, 2000, 133-134, 78-90.	2.2	203
17	A review comparing cathodic arcs and high power impulse magnetron sputtering (HiPIMS). Surface and Coatings Technology, 2014, 257, 308-325.	2.2	200
18	Comparative surface and nano-tribological characteristics of nanocomposite diamond-like carbon thin films doped by silver. Applied Surface Science, 2008, 255, 2551-2556.	3.1	174

#	Article	IF	Citations
19	Transport of vacuum arc plasmas through magnetic macroparticle filters. Plasma Sources Science and Technology, 1995, 4, 1-12.	1.3	173
20	Deposition rates of high power impulse magnetron sputtering: Physics and economics. Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films, 2010, 28, 783-790.	0.9	172
21	Ion charge state distributions in high current vacuum arc plasmas in a magnetic field. IEEE Transactions on Plasma Science, 1996, 24, 1174-1183.	0.6	162
22	Plasma-based ion implantation and deposition: a review of physics, technology, and applications. IEEE Transactions on Plasma Science, 2005, 33, 1944-1959.	0.6	156
23	Metal plasma immersion ion implantation and deposition using vacuum arc plasma sources. Journal of Vacuum Science & Technology an Official Journal of the American Vacuum Society B, Microelectronics Processing and Phenomena, 1994, 12, 815.	1.6	151
24	Drifting localization of ionization runaway: Unraveling the nature of anomalous transport in high power impulse magnetron sputtering. Journal of Applied Physics, 2012, 111, 053304.	1.1	143
25	Pulsed dye laser diagnostics of vacuum arc cathode spots. IEEE Transactions on Plasma Science, 1992, 20, 466-472.	0.6	142
26	The absence of plasma in â€œspark plasma sinteringâ€. Journal of Applied Physics, 2008, 104, .	1.1	142
27	Effect of vacuum arc deposition parameters on the properties of amorphous carbon thin films. Surface and Coatings Technology, 1994, 68-69, 388-393.	2.2	132
28	Resonant Inelastic Scattering Spectra of Free Molecules with Vibrational Resolution. Physical Review Letters, 2010, 104, 193002.	2.9	126
29	Plasma and ion sources in large area coating: A review. Surface and Coatings Technology, 2005, 200, 1893-1906.	2.2	123
30	`Triggerless' triggering of vacuum arcs. Journal Physics D: Applied Physics, 1998, 31, 584-587.	1.3	119
31	Drift Compression of an Intense Neutralized Ion Beam. Physical Review Letters, 2005, 95, 234801.	2.9	118
32	Fundamentals of pulsed plasmas for materials processing. Surface and Coatings Technology, 2004, 183, 301-311.	2.2	116
33	Macroparticleâ€free thin films produced by an efficient vacuum arc deposition technique. Journal of Applied Physics, 1993, 74, 4239-4241.	1.1	107
34	Xiphophorus As An In Vivo Model for Studies on Normal and Defective Control of Oncogenes. Advances in Cancer Research, 1984, 42, 191-275.	1.9	105
35	On the macroparticle flux from vacuum arc cathode spots. IEEE Transactions on Plasma Science, 1993, 21, 440-446.	0.6	103
36	Effect of intrinsic growth stress on the Raman spectra of vacuumâ€arcâ€deposited amorphous carbon films. Applied Physics Letters, 1995, 66, 3444-3446.	1.5	102

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37	Atomic scale heating in cathodic arc plasma deposition. Applied Physics Letters, 2002, 80, 1100-1102.	1.5	98
38	Effect of duct bias on transport of vacuum arc plasmas through curved magnetic filters. Journal of Applied Physics, 1994, 75, 4900-4905.	1.1	96
39	Correlation between cathode properties, burning voltage, and plasma parameters of vacuum arcs. Journal of Applied Physics, 2001, 89, 7764-7771.	1.1	95
40	Energetic deposition using filtered cathodic arc plasmas. Vacuum, 2002, 67, 673-686.	1.6	92
41	Structure and properties of silver-containing a-C(H) films deposited by plasma immersion ion implantation. Surface and Coatings Technology, 2008, 202, 3675-3682.	2.2	87
42	The â€˜recycling trapâ€™: a generalized explanation of discharge runaway in high-power impulse magnetron sputtering. Journal Physics D: Applied Physics, 2012, 45, 012003.	1.3	85
43	Measurements of the total ion flux from vacuum arc cathode spots. IEEE Transactions on Plasma Science, 2005, 33, 1532-1536.	0.6	84
44	Self-sputtering runaway in high power impulse magnetron sputtering: The role of secondary electrons and multiply charged metal ions. Applied Physics Letters, 2008, 92, .	1.5	84
45	Plasma synthesis of metallic and composite thin films with atomically mixed substrate bonding. Nuclear Instruments & Methods in Physics Research B, 1993, 80-81, 1281-1287.	0.6	83
46	Streaming metal plasma generation by vacuum arc plasma guns. Review of Scientific Instruments, 1998, 69, 801-803.	0.6	83
47	Gas rarefaction and the time evolution of long high-power impulse magnetron sputtering pulses. Plasma Sources Science and Technology, 2012, 21, 045004.	1.3	82
48	Ion energy distribution functions of vacuum arc plasmas. Journal of Applied Physics, 2003, 93, 1899-1906.	1.1	81
49	From plasma immersion ion implantation to deposition: a historical perspective on principles and trends. Surface and Coatings Technology, 2002, 156, 3-12.	2.2	79
50	Physics of arcing, and implications to sputter deposition. Thin Solid Films, 2006, 502, 22-28.	0.8	78
51	A Theoretical Analysis of Vacuum Arc Thruster and Vacuum Arc Ion Thruster Performance. IEEE Transactions on Plasma Science, 2008, 36, 2167-2179.	0.6	76
52	Plasma potential mapping of high power impulse magnetron sputtering discharges. Journal of Applied Physics, 2012, 111, .	1.1	75
53	Drifting potential humps in ionization zones: The â€œpropeller bladesâ€•of high power impulse magnetron sputtering. Applied Physics Letters, 2013, 103, .	1.5	75
54	Hydrogen uptake in alumina thin films synthesized from an aluminum plasma stream in an oxygen ambient. Applied Physics Letters, 1999, 74, 200-202.	1.5	73

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55	Metal plasmas for the fabrication of nanostructures. Journal Physics D: Applied Physics, 2007, 40, 2272-2284.	1.3	73
56	Compression and strong rarefaction in high power impulse magnetron sputtering discharges. Journal of Applied Physics, 2010, 108, .	1.1	73
57	Self-organization and self-limitation in high power impulse magnetron sputtering. Applied Physics Letters, 2012, 100, .	1.5	73
58	Self-Sputtering Far above the Runaway Threshold: An Extraordinary Metal-Ion Generator. Physical Review Letters, 2009, 102, 045003.	2.9	72
59	On sheath energization and Ohmic heating in sputtering magnetrons. Plasma Sources Science and Technology, 2013, 22, 045005.	1.3	72
60	Gasless sputtering: Opportunities for ultraclean metallization, coatings in space, and propulsion. Applied Physics Letters, 2008, 92, .	1.5	71
61	Origin of the Delayed Current Onset in High-Power Impulse Magnetron Sputtering. IEEE Transactions on Plasma Science, 2010, 38, 3028-3034.	0.6	71
62	S-shaped magnetic macroparticle filter for cathodic arc deposition. IEEE Transactions on Plasma Science, 1997, 25, 670-674.	0.6	69
63	Inductive energy storage driven vacuum arc thruster. Review of Scientific Instruments, 2002, 73, 925-927.	0.6	69
64	Plasma potential of a moving ionization zone in DC magnetron sputtering. Journal of Applied Physics, 2017, 121, .	1.1	69
65	The working principle of the hollow-anode plasma source. Plasma Sources Science and Technology, 1995, 4, 571-575.	1.3	68
66	The fractal nature of vacuum arc cathode spots. IEEE Transactions on Plasma Science, 2005, 33, 1456-1464.	0.6	67
67	Smoothing of ultrathin silver films by transition metal seeding. Solid State Communications, 2006, 140, 225-229.	0.9	67
68	On modes of arc cathode operation. IEEE Transactions on Plasma Science, 1991, 19, 20-24.	0.6	66
69	Results on intense beam focusing and neutralization from the neutralized beam experiment. Physics of Plasmas, 2004, 11, 2890-2898.	0.7	64
70	The evolution of ion charge states in cathodic vacuum arc plasmas: a review. Plasma Sources Science and Technology, 2012, 21, 035014.	1.3	62
71	Time dependence of vacuum arc parameters. IEEE Transactions on Plasma Science, 1993, 21, 305-311.	0.6	60
72	Recent advances in surface processing with metal plasma and ion beams. Surface and Coatings Technology, 1999, 112, 271-277.	2.2	60

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73	Crystal structure and properties of CdxZn1âˆ'xO alloys across the full composition range. Applied Physics Letters, 2013, 102, .	1.5	60
74	Room Temperature Oxide Deposition Approach to Fully Transparent, Allâ€Oxide Thinâ€Film Transistors. Advanced Materials, 2015, 27, 6090-6095.	11.1	57
75	Emission spectroscopy of low-current vacuum arcs. Journal Physics D: Applied Physics, 1991, 24, 1986-1992.	1.3	56
76	Pulsed vacuum-arc ion source operated with a â€œtriggerlessâ€• arc initiation method. Review of Scientific Instruments, 2000, 71, 827-829.	0.6	56
77	Observation of Ti4+ ions in a high power impulse magnetron sputtering plasma. Applied Physics Letters, 2008, 93, .	1.5	56
78	Ultrathin diamond-like carbon films deposited by filtered carbon vacuum arcs. IEEE Transactions on Plasma Science, 2001, 29, 768-775.	0.6	55
79	Transparent and conductive indium doped cadmium oxide thin films prepared by pulsed filtered cathodic arc deposition. Applied Surface Science, 2013, 265, 738-744.	3.1	55
80	On the road to self-sputtering in high power impulse magnetron sputtering: particle balance and discharge characteristics. Plasma Sources Science and Technology, 2014, 23, 025017.	1.3	55
81	Focused injection of vacuum arc plasmas into curved magnetic filters. Journal of Applied Physics, 1994, 75, 4895-4899.	1.1	54
82	Macroparticle filtering of high-current vacuum arc plasmas. IEEE Transactions on Plasma Science, 1997, 25, 660-664.	0.6	54
83	A periodic table of ion charge-state distributions observed in the transition region between vacuum sparks and vacuum arcs. IEEE Transactions on Plasma Science, 2001, 29, 393-398.	0.6	54
84	Self-sustained self-sputtering: a possible mechanism for the superdense glow phase of a pseudospark. IEEE Transactions on Plasma Science, 1995, 23, 275-282.	0.6	53
85	Coalescence of nanometer silver islands on oxides grown by filtered cathodic arc deposition. Applied Physics Letters, 2003, 82, 1634-1636.	1.5	53
86	Production of neutrals and their effects on the ion charge states in cathodic vacuum arc plasmas. Journal of Applied Physics, 2007, 102, .	1.1	53
87	Genetic basis of susceptibility for development of neoplasms following treatment with N-methyl-N-nitrosourea (MNU) or X-rays in the platyfish/swordtail system. Experientia, 1978, 34, 780-782.	1.2	51
88	Frozen state of ionisation in a cathodic plasma jet of a vacuum arc. Journal Physics D: Applied Physics, 1988, 21, 213-215.	1.3	51
89	Effect of the pulse repetition rate on the composition and ion charge-state distribution of pulsed vacuum arcs. IEEE Transactions on Plasma Science, 1998, 26, 220-226.	0.6	51
90	Cathodic arcs: Fractal voltage and cohesive energy rule. Applied Physics Letters, 2005, 86, 211503.	1.5	51

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91	High power impulse magnetron sputtering and related discharges: Scalable plasma sources for plasma-based ion implantation and deposition. Surface and Coatings Technology, 2010, 204, 2864-2868.	2.2	51
92	Spectroscopic imaging of self-organization in high power impulse magnetron sputtering plasmas. Applied Physics Letters, 2013, 103, .	1.5	51
93	Localized heating of electrons in ionization zones: Going beyond the Penning-Thornton paradigm in magnetron sputtering. Applied Physics Letters, 2014, 105, 244104.	1.5	51
94	Width, structure and stability of sheaths in metal plasma immersion ion implantation and deposition: measurements and analytical considerations. Surface and Coatings Technology, 2001, 136, 85-92.	2.2	50
95	Asymmetric particle fluxes from drifting ionization zones in sputtering magnetrons. Plasma Sources Science and Technology, 2014, 23, 025007.	1.3	49
96	Model for explosive electron emission in a pseudospark â€˜â€˜superdense glowâ€™â€™. Physical Review Letters, 1993, 71, 364-367.	2.9	48
97	Magnetic field effect on the sheath thickness in plasma immersion ion implantation. Applied Physics Letters, 2002, 81, 1183-1185.	1.5	48
98	High quality ZnO:Al transparent conducting oxide films synthesized by pulsed filtered cathodic arc deposition. Thin Solid Films, 2010, 518, 3313-3319.	0.8	48
99	Ion charge state distributions of pulsed vacuum arc plasmas in strong magnetic fields. Review of Scientific Instruments, 1998, 69, 1332-1335.	0.6	46
100	Optimizing the deposition rate and ionized flux fraction by tuning the pulse length in high power impulse magnetron sputtering. Plasma Sources Science and Technology, 2020, 29, 05LT01.	1.3	46
101	Formation of metal oxides by cathodic arc deposition. Surface and Coatings Technology, 1995, 76-77, 167-173.	2.2	45
102	Recent advances in vacuum arc ion sources. Surface and Coatings Technology, 1996, 84, 550-556.	2.2	45
103	Progress in beam focusing and compression for warm-dense matter experiments. Nuclear Instruments and Methods in Physics Research, Section A: Accelerators, Spectrometers, Detectors and Associated Equipment, 2009, 606, 75-82.	0.7	45
104	Plasma flares in high power impulse magnetron sputtering. Applied Physics Letters, 2012, 101, .	1.5	45
105	Brightness distribution and current density of vacuum arc cathode spots. Journal Physics D: Applied Physics, 1992, 25, 1591-1599.	1.3	44
106	Enhanced ion charge states in vacuum arc plasmas using a â€œcurrent spikeâ€•method. Review of Scientific Instruments, 2000, 71, 701-703.	0.6	44
107	Angularly resolved measurements of ion energy of vacuum arc plasmas. Applied Physics Letters, 2002, 80, 2457-2459.	1.5	44
108	Etiology of cancer as studied in the platyfish-swordtail system. Biochimica Et Biophysica Acta: Reviews on Cancer, 1978, 516, 61-95.	3.3	43

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109	Electron emission from pseudospark cathodes. Journal of Applied Physics, 1994, 76, 1494-1502.	1.1	43
110	Structural, optical, and electrical properties of WOx(Ny) films deposited by reactive dual magnetron sputtering. Surface and Coatings Technology, 2006, 201, 2977-2983.	2.2	43
111	Extractable, elevated ion charge states in the transition regime from vacuum sparks to high current vacuum arcs. Applied Physics Letters, 2008, 92, .	1.5	43
112	Twist filter for the removal of macroparticles from cathodic arc plasmas. Surface and Coatings Technology, 2000, 133-134, 96-100.	2.2	42
113	Spatial distribution of average charge state and deposition rate in high power impulse magnetron sputtering of copper. Journal Physics D: Applied Physics, 2008, 41, 135210.	1.3	42
114	Determining the nonparabolicity factor of the CdO conduction band using indium doping and the Drude theory. Journal Physics D: Applied Physics, 2012, 45, 425302.	1.3	42
115	Insights into â€œnear-frictionless carbon filmsâ€. Journal of Applied Physics, 2004, 95, 7765-7771.	1.1	40
116	Growth and decay of macroparticles: A feasible approach to clean vacuum arc plasmas?. Journal of Applied Physics, 1997, 82, 3679-3688.	1.1	39
117	Charge-state-resolved ion energy distribution functions of cathodic vacuum arcs: A study involving the plasma potential and biased plasmas. Journal of Applied Physics, 2007, 101, 043304.	1.1	39
118	Pressure ionization: its role in metal vapour vacuum arc plasmas and ion sources. Plasma Sources Science and Technology, 1992, 1, 263-270.	1.3	38
119	Characterization of a low-energy constricted-plasma source. Review of Scientific Instruments, 1998, 69, 1340-1343.	0.6	38
120	Effect of multiple current spikes on the enhancement of ion charge states of vacuum arc plasmas. Journal of Applied Physics, 2000, 87, 8345-8350.	1.1	38
121	Coalescence of magnetron-sputtered silver islands affected by transition metal seeding (Ni, Cr, Nb, Zr,) Tj ETQq1 1 0.784314 rgBT /Ov	0.8	38
122	Local Electronic Structure of Functional Groups in Glycine As Anion, Zwitterion, and Cation in Aqueous Solution. Journal of Physical Chemistry B, 2009, 113, 16002-16006.	1.2	38
123	Plasma â€œanti-assistanceâ€and â€œself-assistanceâ€to high power impulse magnetron sputtering. Journal of Applied Physics, 2009, 105, .	1.1	38
124	Micro-propulsion based on vacuum arcs. Journal of Applied Physics, 2019, 125, .	1.1	38
125	Evolution of the plasma composition of a high power impulse magnetron sputtering system studied with a time-of-flight spectrometer. Journal of Applied Physics, 2009, 105, .	1.1	37
126	Fermi level stabilization and band edge energies in CdxZn1â^'xO alloys. Journal of Applied Physics, 2014, 115, .	1.1	37

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127	Design and characterization of a neutralized-transport experiment for heavy-ion fusion. Physical Review Special Topics: Accelerators and Beams, 2004, 7, .	1.8	36
128	Propagation direction reversal of ionization zones in the transition between high and low current magnetron sputtering. Applied Physics Letters, 2014, 105, .	1.5	36
129	Metal ion implantation: Conventional versus immersion. Journal of Vacuum Science & Technology an Official Journal of the American Vacuum Society B, Microelectronics Processing and Phenomena, 1994, 12, 823.	1.6	35
130	Charge-state-resolved ion energy distributions of aluminum vacuum arcs in the absence and presence of a magnetic field. Journal of Applied Physics, 2005, 97, 103306.	1.1	35
131	Dopant-induced band filling and bandgap renormalization in CdOâ€‰:â€‰In films. Journal Physics D: Applied Physics, 2013, 46, 195102.	1.3	35
132	Hollowâ€anode plasma source for molecular beam epitaxy of gallium nitride. Review of Scientific Instruments, 1996, 67, 905-907.	0.6	34
133	Influence of argon and oxygen on charge-state-resolved ion energy distributions of filtered aluminum arcs. Journal of Applied Physics, 2006, 99, 123303.	1.1	34
134	On the deactivation of the dopant and electronic structure in reactively sputtered transparent Al-doped ZnO thin films. Journal Physics D: Applied Physics, 2010, 43, 132003.	1.3	34
135	Achieving high mobility ZnOâ€‰:â€‰Al at very high growth rates by dc filtered cathodic arc deposition. Journal Physics D: Applied Physics, 2011, 44, 232003.	1.3	34
136	Chemistry, phase formation, and catalytic activity of thin palladium-containing oxide films synthesized by plasma-assisted physical vapor deposition. Surface and Coatings Technology, 2011, 205, S171-S177.	2.2	33
137	Evaluation of species-specific score cutoff values of routinely isolated clinically relevant bacteria using a direct smear preparation for matrix-assisted laser desorption/ionization time-of-flight mass spectrometry-based bacterial identification. European Journal of Clinical Microbiology and Infectious Diseases, 2012, 31, 1109-1119.	1.3	33
138	Temporal development of the plasma composition of a pulsed aluminum plasma stream in the presence of oxygen. Applied Physics Letters, 1999, 75, 612-614.	1.5	32
139	Designing advanced filters for macroparticle removal from cathodic arc plasmas. Plasma Sources Science and Technology, 1999, 8, 488-493.	1.3	32
140	Electronic structure and conductivity of nanocomposite metal (Au, Ag, Cu, Mo)-containing amorphous carbon films. Solid State Sciences, 2009, 11, 1742-1746.	1.5	32
141	Modeling of optical and energy performance of tungsten-oxide-based electrochromic windows including their intermediate states. Solar Energy Materials and Solar Cells, 2013, 108, 129-135.	3.0	32
142	High ion charge states in a highâ€current, shortâ€pulse, vacuum arc ion source. Review of Scientific Instruments, 1996, 67, 1202-1204.	0.6	31
143	Plasma fluctuations, local partial Saha equilibrium, and the broadening of vacuum-arc ion charge state distributions. IEEE Transactions on Plasma Science, 1999, 27, 1060-1067.	0.6	31
144	Tracking down the origin of arc plasma science-II. early continuous discharges. IEEE Transactions on Plasma Science, 2003, 31, 1060-1069.	0.6	31

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145	Velocity distribution of carbon macroparticles generated by pulsed vacuum arcs. Plasma Sources Science and Technology, 1999, 8, 567-571.	1.3	30
146	Efficient, compact power supply for repetitively pulsed, â€œtriggerlessâ€•cathodic arcs. Review of Scientific Instruments, 1999, 70, 4532-4535.	0.6	29
147	Magnetic-field-dependent plasma composition of a pulsed aluminum arc in an oxygen ambient. Applied Physics Letters, 2001, 78, 150-152.	1.5	29
148	Observation of self-sputtering in energetic condensation of metal ions. Applied Physics Letters, 2004, 85, 6137-6139.	1.5	29
149	Vacuum arc cathode spot parameters from highâ€resolution luminosity measurements. Journal of Applied Physics, 1992, 71, 4763-4770.	1.1	28
150	Breakdown of the high-voltage sheath in metal plasma immersion ion implantation. Applied Physics Letters, 2000, 76, 28-30.	1.5	28
151	Time-dependence of ion charge State distributions of vacuum arcs: an interpretation involving atoms and charge exchange collisions. IEEE Transactions on Plasma Science, 2005, 33, 205-209.	0.6	28
152	Charge state dependence of cathodic vacuum arc ion energy and velocity distributions. Applied Physics Letters, 2006, 89, 141502.	1.5	28
153	Filtered cathodic arc deposition with ion-species-selective bias. Review of Scientific Instruments, 2007, 78, 063901.	0.6	28
154	Mo-containing tetrahedral amorphous carbon deposited by dual filtered cathodic vacuum arc with selective pulsed bias voltage. Nuclear Instruments & Methods in Physics Research B, 2007, 259, 867-870.	0.6	28
155	Structural, optical, and electrical properties of indium-doped cadmium oxide films prepared by pulsed filtered cathodic arc deposition. Journal of Materials Science, 2013, 48, 3789-3797.	1.7	28
156	Influence of ionisation zone motion in high power impulse magnetron sputtering on angular ion flux and NbO_{<i>x</i>}film growth. Plasma Sources Science and Technology, 2016, 25, 015022.	1.3	28
157	Phase tailoring of tantalum thin films deposited in deep oscillation magnetron sputtering mode. Surface and Coatings Technology, 2017, 314, 97-104.	2.2	27
158	Reduced atomic shadowing in HiPIMS: Role of the thermalized metal ions. Applied Surface Science, 2018, 433, 934-944.	3.1	27
159	Foundations of physical vapor deposition with plasma assistance. Plasma Sources Science and Technology, 2022, 31, 083001.	1.3	27
160	Puzzling differences in bismuth and lead plasmas: Evidence for the significant role of neutrals in cathodic vacuum arcs. Applied Physics Letters, 2007, 91, .	1.5	25
161	Ion energies in high power impulse magnetron sputtering with and without localized ionization zones. Applied Physics Letters, 2015, 106, .	1.5	25
162	Genetics of susceptibility in the platyfish/swordtail tumor system to develop fibrosarcoma and rhabdomyosarcoma following treatment with N-methyl-N-nitrosourea (MNU). Zeitschrift FÃ¼r Krebsforschung Und Klinische Onkologie, 1978, 91, 301-315.	0.8	24

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163	High-resolution imaging of vacuum arc cathode spots. IEEE Transactions on Plasma Science, 1996, 24, 69-70.	0.6	24
164	Spectra and energy levels of Yb3+ in AlN. Journal of Applied Physics, 2009, 106, 013106.	1.1	24
165	Direct observation of spoke evolution in magnetron sputtering. Applied Physics Letters, 2017, 111, .	1.5	24
166	Effects of Nonâ€Ideality and Nonâ€Equilibrium in the Cathode Spot Plasma of Vacuum Arcs. Contributions To Plasma Physics, 1989, 29, 537-543.	0.5	23
167	Neutralized transport experiment. Nuclear Instruments and Methods in Physics Research, Section A: Accelerators, Spectrometers, Detectors and Associated Equipment, 2005, 544, 225-235.	0.7	23
168	A space-charge-neutralizing plasma for beam drift compression. Nuclear Instruments and Methods in Physics Research, Section A: Accelerators, Spectrometers, Detectors and Associated Equipment, 2009, 606, 22-30.	0.7	23
169	Distance-dependent plasma composition and ion energy in high power impulse magnetron sputtering. Journal Physics D: Applied Physics, 2010, 43, 275204.	1.3	23
170	Models of DNA-dye-complexes: Energy transfer and molecular structures as evaluated by laser excitation. Applied Physics Berlin, 1979, 18, 333-338.	1.4	22
171	Measurement of total ion current from vacuum arc plasma sources. Review of Scientific Instruments, 2006, 77, 03B504.	0.6	22
172	Observation of multiple charge states and high ion energies in high-power impulse magnetron sputtering (HiPIMS) and burst HiPIMS using a LaB₆target. Plasma Sources Science and Technology, 2014, 23, 035001.	1.3	22
173	Vacuum arc ion sources: Some vacuum arc basics and recent results (invited). Review of Scientific Instruments, 1994, 65, 1253-1258.	0.6	21
174	Increasing the retained dose by plasma immersion ion implantation and deposition. Nuclear Instruments & Methods in Physics Research B, 1995, 102, 132-135.	0.6	21
175	Energetics of vacuum arc cathode spots. Applied Physics Letters, 2001, 78, 2837-2839.	1.5	21
176	Tracking down the origin of arc plasma science I. early pulsed and oscillating discharges. IEEE Transactions on Plasma Science, 2003, 31, 1052-1059.	0.6	21
177	Time and material dependence of the voltage noise generated by cathodic vacuum arcs. Journal Physics D: Applied Physics, 2005, 38, 4184-4190.	1.3	21
178	Plasma biasing to control the growth conditions of diamond-like carbon. Surface and Coatings Technology, 2007, 201, 4628-4632.	2.2	21
179	Ion acceleration and cooling in gasless self-sputtering. Applied Physics Letters, 2010, 97, .	1.5	21
180	Epitaxy of Ultrathin NiSi2 Films with Predetermined Thickness. Electrochemical and Solid-State Letters, 2011, 14, H268.	2.2	21

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181	2-D mathematical modeling for a large electrochromic windowâ€”Part I. Solar Energy Materials and Solar Cells, 2014, 120, 1-8.	3.0	21
182	Evidence for breathing modes in direct current, pulsed, and high power impulse magnetron sputtering plasmas. Applied Physics Letters, 2016, 108, .	1.5	21
183	Plasma studies of a linear magnetron operating in the range from DC to HiPIMS. Journal of Applied Physics, 2018, 123, 043302.	1.1	21
184	Surface modification of magnetic recording heads by plasma immersion ion implantation and deposition. Journal of Applied Physics, 1994, 76, 1656-1664.	1.1	20
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